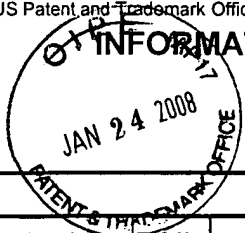


FORM PTO-1449 (Modified)		US DEPARTMENT OF COMMERCE		Docket No. 050623.61	Application No. 09/997,450
US Patent and Trademark Office		INFORMATION DISCLOSURE CITATION in an Application (Use several sheets if necessary)			
					
		Applicant Shamim Malik et al.		Filing Date November 30, 2001	Group Art Unit 3731

U.S. PATENT DOCUMENTS

Examiner Initial	Ref. No.	Document Number	Date of Patent	Name	Class	Subclass	Filing Date if Appropriate
	A1	4,486,247	12/4/84	Ecer et al.			
	A2	5,040,548	8/20/91	Yock			
	A3	5,047,050	9/10/91	Arpesani			
	A4	5,049,132	9/17/91	Shaffer et al.			
	A5	5,084,151	1/28/92	Vallana et al.			
	A6	5,165,919	11/24/92	Sasaki et al.			
	A7	5,192,311	3/9/93	King et al.			
	A8	5,188,734	12/23/93	Zepf			
	A9	5,415,704	5/16/95	Davidson			
	A10	5,925,552	7/20/99	Keogh et al.			
	A11	6,273,913	8/14/01	Wright et al.			
	A12	6,273,908	8/14/01	Ndondo-Lay			
	A13	6,335,029	1/1/02	Kamath et al.			
	A14	6,613,432	9/2/03	Zamora et al.			
	A15	7,056,523	6/6/06	Michal et al.			
	A16	7,077,860	7/18/06	Yan et al.			
	A17	7,163,165	1/16/07	Paul et al.			
	A18	7,163,715	1/16/07	Kramer			
	A19	7,201,940	4/10/07	Kramer			

U.S. PATENT APPLICATION DOCUMENTS

Examiner Initial	Ref. No.	Document Number	Filing Date	Name	Class	Subclass	Publication Date if Appropriate
	A20	09/997,449	11/30/01	Malik et al.			
	A21	10/672,890	9/26/03	Malik et al.			

U.S. PATENT APPLICATION PUBLICATION DOCUMENTS

Examiner Initial	Ref. No.	Document Number	Date of Publication	Name	Class	Subclass	Filing Date if Appropriate
	A22	20060178738	8/10/06	Yan et al.			
	A23	20070036905	2/15/07	Kramer			

	A24	20070166496	7/19/07	Kramer				
	A25	20070184228	8/9/07	Kramer				
FOREIGN PATENT DOCUMENTS								
Examiner	Ref. No.	Document	Date of	Country	Class	Subclass	Translation	
Initial		Number	Publication				Abstract	
							Yes	No
	B1	DE 19855786	6/8/00	Germany			X	
	B2							
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)								
	C1	Malik et al., <i>Development of an Energetic Ion Assisted Mixing and Deposition Process for TIN_x and Diamondlike Carbon Films, Using a Co-axial Geometry in Plasma Source Ion Implantation</i> , J. Vac. Sci. Technol. A, Vol. 15, No. 6, pp. 2875-2879 (Nov./Dec. 1997).						
	C2	Malik et al., <i>Overview of plasma source ion implantation research at University of Wisconsin-Madison</i> , J. Vac. Sci. Technol. B, No. 12, Vol. 2, pp. 843-849 (Mar./Apr. 1994).						
	C3	Malik et al., <i>Sheath dynamics and dose analysis for planar targets in plasma source ion implantation</i> , Plasma Sources Sci. Technol. Vol. 2, pp. 81-85 (1993).						
	C4	Scheuer et al., <i>Model of plasma source ion implantation in planar, cylindrical, and spherical geometries</i> , J. Appl. Phys., Vol. 67, No. 3, pp. 1241-1245 (Feb. 1990).						
	C5	Shamim et al., <i>Measurement of electron emission due to energetic ion bombardment in plasma source ion implantation</i> , J. Appl. Phys., Vol. 70, No. 9, pp. 4756-4759 (Nov. 1991).						
	C6	Shamim et al., <i>Measurements of Spatial and Temporal Sheath Evolution for Spherical and Cylindrical Geometries in Plasma Source Ion Implantation</i> , J. Appl. Phys., Vol. 69, No. 5, pp. 2904-2908 (March 1991).						
EXAMINER				DATE CONSIDERED				
EXAMINER: Initial if references considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								